

10673820_CLS
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10673820 on March 17, 2004

Original Classifications

4 430/5
3 250/491.1
2 250/492.3
2 355/53
2 427/498
2 430/296

Cross-Reference Classifications

5 250/492.2
3 427/407.1
3 427/496
3 427/504
3 427/526
3 430/942
2 250/396R
2 250/492.22
2 250/492.3
2 250/505.1
2 313/309
2 315/5.31
2 369/103
2 369/44.12
2 369/44.23
2 427/259
2 427/264
2 427/525
2 427/533
2 427/552
2 430/296
2 430/945
2 438/933

Combined Classifications

6 250/492.2
4 250/492.3
4 430/296
4 430/5
3 250/491.1
3 250/492.22
3 369/103
3 369/44.12
3 427/407.1
3 427/496

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3 427/504
3 427/526
3 430/942
2 250/396R
2 250/505.1
2 313/309
2 313/336
2 315/5.31
2 355/53
2 369/100
2 369/44.23
2 427/259
2 427/264
2 427/498
2 427/525
2 427/533
2 427/552
2 430/945
2 438/87
2 438/933

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Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10673820 on March 17, 2004

6	250/492.2	(1 OR, 5 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
4	250/492.3	(2 OR, 2 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.3	.Ion or electron beam irradiation
4	430/296	(2 OR, 2 XR)
	Class 430 :	RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
	430/269	IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
	430/296	.Electron beam imaging
4	430/5	(4 OR, 0 XR)
	Class 430 :	RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
	430/4	RADIATION MODIFYING PRODUCT OR PROCESS OF MAKING
	430/5	.Radiation mask
3	250/491.1	(3 OR, 0 XR)
	Class 250 :	RADIANT ENERGY
	250/491.1	MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE TO A SOURCE OR DETECTOR
3	250/492.22	(1 OR, 2 XR)
	Class 250 :	RADIANT ENERGY
	250/492.1	IRRADIATION OF OBJECTS OR MATERIAL
	250/492.2	.Irradiation of semiconductor devices
	250/492.22	..Pattern control
3	369/103	(1 OR, 2 XR)
	Class 369 :	DYNAMIC INFORMATION STORAGE OR RETRIEVAL SPECIFIC DETAIL OF INFORMATION HANDLING PORTION OF SYSTEM
	369/99	

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369/100 .Radiation beam modification of or by storage
medium

369/103 ..Holographic

3 369/44.12 (1 OR, 2 XR)
Class 369 : DYNAMIC INFORMATION STORAGE OR RETRIEVAL
369/43 WITH SERVO POSITIONING OF TRANSDUCER ASSEMBLY
OVER TRACK COMBINED WITH INFORMATION SIGN
AL PROCESSING

369/44.11 .Optical servo system

369/44.12 ..Solid state optical element with plural
dissimilar optical components (e.g., using
I.C. block,
etc.)

3 427/407.1 (0 OR, 3 XR)
Class 427 : COATING PROCESSES
427/402 APPLYING SUPERPOSED DIVERSE COATING OR COATING
A COATED BASE
427/407.1 .Synthetic resin coating

3 427/496 (0 OR, 3 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/487 .Polymerization of coating utilizing direct
application of electrical, magnetic, wave,
or particulate
energy (i.e., including cross-linking, cur
ing, and
hardening of organics)

427/496 ..High energy electromagnetic radiation or hig
h
energy particles utilized (e.g., gamma rays
, X-rays, atomic
particles, i.e., alpha rays, beta rays, ele
ctrons, etc.)

3 427/504 (0 OR, 3 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/487 .Polymerization of coating utilizing direct
application of electrical, magnetic, wave
, or particulate
energy (i.e., including cross-linking, cu
ring, and
hardening of organics)

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427/496 ..High energy electromagnetic radiation or high energy particles utilized (e.g., gamma rays, X-rays, atomic particles, i.e., alpha rays, beta rays, electrons, etc.)

427/504 ...Nonuniform or patterned coating (e.g., mask printing, etc.)

3 427/526 (0 OR, 3 XR)
 Class 427 : COATING PROCESSES
 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR PARTICULATE ENERGY
 427/523 .Ion plating or implantation
 427/526 ..Nonuniform or patterned ion plating or ion implanting (e.g., mask, etc.)

3 430/942 (0 OR, 3 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
 430/942 ELECTRON BEAM

2 250/396R (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSING

2 250/505.1 (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/505.1 RADIATION CONTROLLING MEANS

2 313/309 (0 OR, 2 XR)
 Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
 313/309 DISCHARGE DEVICES HAVING A MULTIPOINTED OR SERRATED EDGE ELECTRODE

2 313/336 (1 OR, 1 XR)
 Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
 313/326 ELECTRODE AND SHIELD STRUCTURES
 313/336 .Point source cathodes

2 315/5.31 (0 OR, 2 XR)
 Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS
 315/1 CATHODE RAY TUBE CIRCUITS
 315/3 .Combined cathode ray tube and circuit element structure

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315/4 ..Inductor or distributed parameter-type
inductive structure

315/5 ...Ray passes in or through a hollow
distributed parameter device

315/5.29Ray has appreciable transverse electrical
dimension and/or significant shape

315/5.31Hollow ray

2 355/53 (2 OR, 0 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/53 .Step and repeat

2 369/100 (1 OR, 1 XR)
Class 369 : DYNAMIC INFORMATION STORAGE OR RETRIEVAL
369/99 SPECIFIC DETAIL OF INFORMATION HANDLING PORTIO

N OF SYSTEM
369/100 .Radiation beam modification of or by storage
medium

2 369/44.23 (0 OR, 2 XR)
Class 369 : DYNAMIC INFORMATION STORAGE OR RETRIEVAL
369/43 WITH SERVO POSITIONING OF TRANSDUCER ASSEMBLY
OVER TRACK COMBINED WITH INFORMATION SIG

NAL PROCESSING
369/44.11 .Optical servo system
369/44.14 ..Optical head servo system structure
369/44.23 ...Structure for shaping beam or causing
astigmatic condition

2 427/259 (0 OR, 2 XR)
Class 427 : COATING PROCESSES
427/256 NONUNIFORM COATING
427/258 .Applying superposed diverse coatings or
coating a coated base
427/259 ..Including a masking coating

2 427/264 (0 OR, 2 XR)
Class 427 : COATING PROCESSES
427/256 NONUNIFORM COATING
427/258 .Applying superposed diverse coatings or
coating a coated base
427/261 ..Final coating nonuniform
427/264 ...Deforming the base or coating or removing a
portion of the coating

2 427/498 (2 OR, 0 XR)

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Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY

427/487 .Polymerization of coating utilizing direct
application of electrical, magnetic, wave
, or particulate
energy (i.e., including cross-linking, cu
ring, and
hardening of organics)

427/496 ..High energy electromagnetic radiation or hig
h
energy particles utilized (e.g., gamma ray
s, X-rays, atomic
particles, i.e., alpha rays, beta rays, el
ectrons, etc.)

427/498 ...Immersion, partial immersion, spraying, or
spin coating utilized (e.g., dipping, etc.)

2 427/525 (0 OR, 2 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY

427/523 .Ion plating or implantation

427/525 ..Organic material present in substrate,
plating, or implanted layer

2 427/533 (0 OR, 2 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY

427/532 .Pretreatment of substrate or post-treatment o
f
coated substrate

427/533 ..Ionized gas utilized (e.g., electrically
powered source, corona discharge, plasma, g
low discharge,
etc.)

2 427/552 (0 OR, 2 XR)

Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY

427/532 .Pretreatment of substrate or post-treatment o
f
coated substrate

427/551 ..High energy electromagnetic radiation or hig
h

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energy particles utilized (e.g., gamma ray
, X-ray, atomic
particle, i.e., alpha ray, beta ray, high
energy electron,
etc.)
427/552 ...Nonuniform or patterned coating

2 430/945 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/945 LASER BEAM

2 438/87 (1 OR, 1 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
438/51 ..Packaging (e.g., with mounting,
encapsulating, etc.) or treatment of pac
kaged
semiconductor
438/57 .Responsive to electromagnetic radiation
438/87 ..Graded composition

2 438/933 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
438/933 GERMANIUM OR SILICON OR GE-SI ON III-V